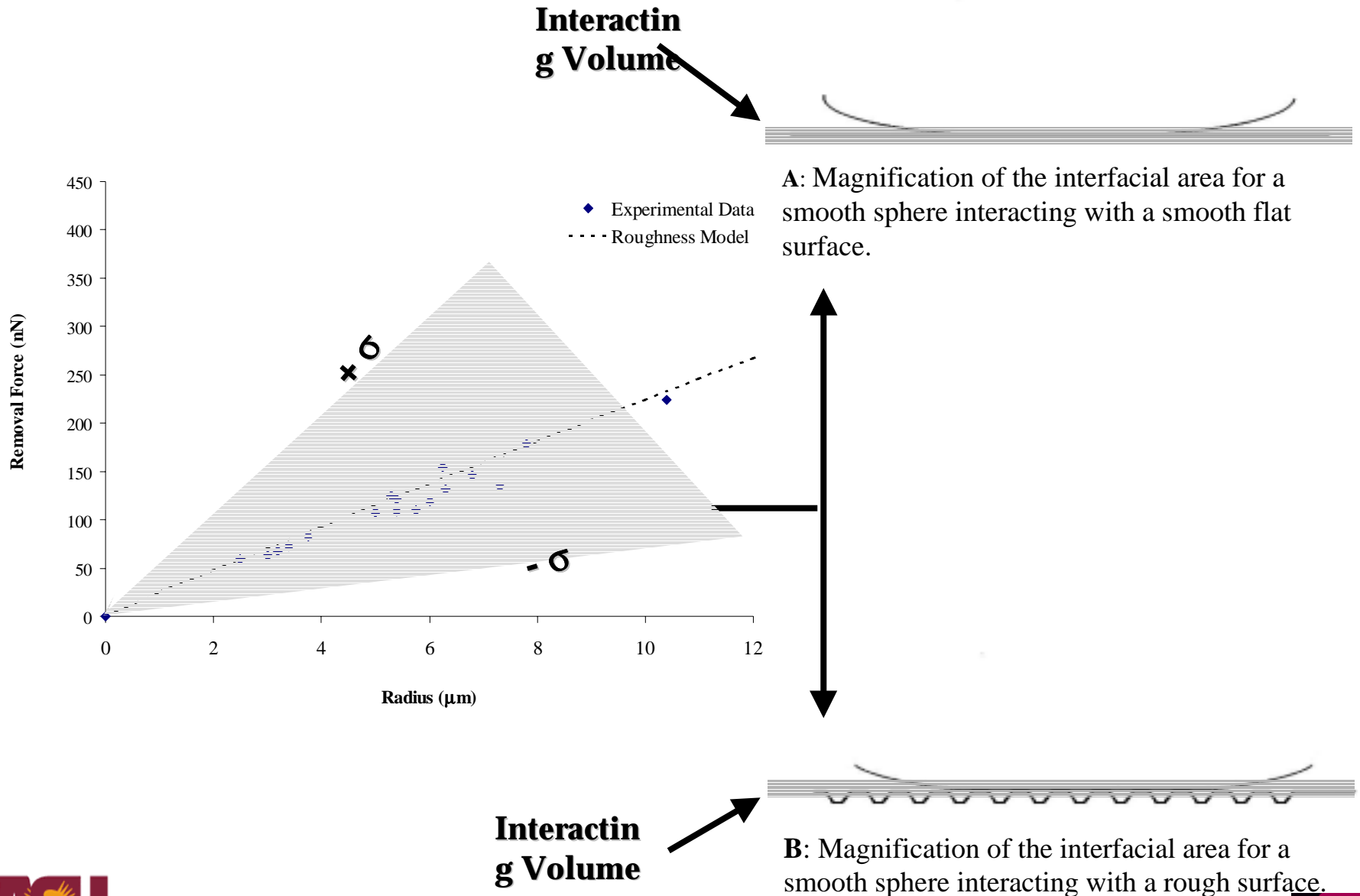
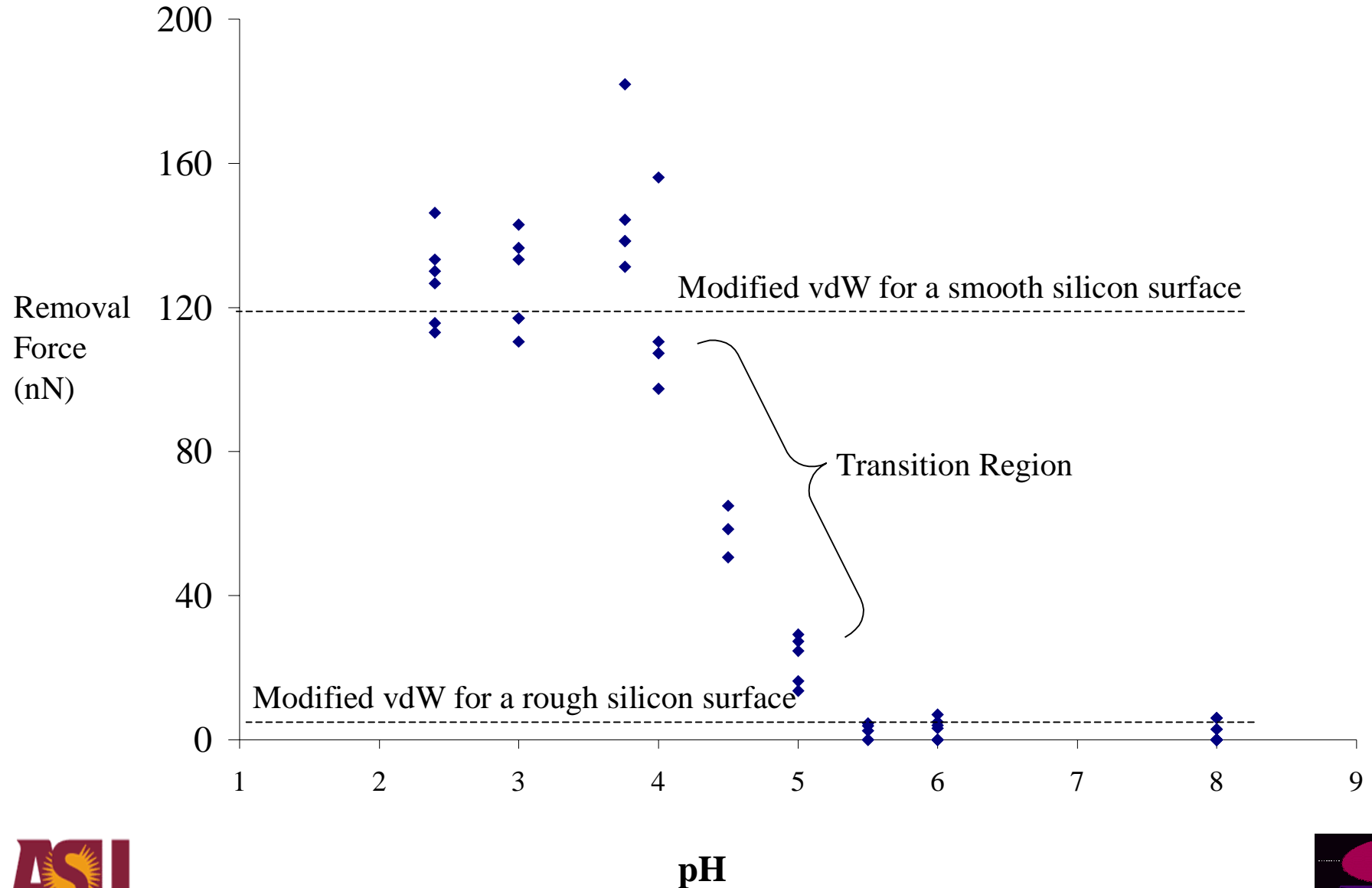


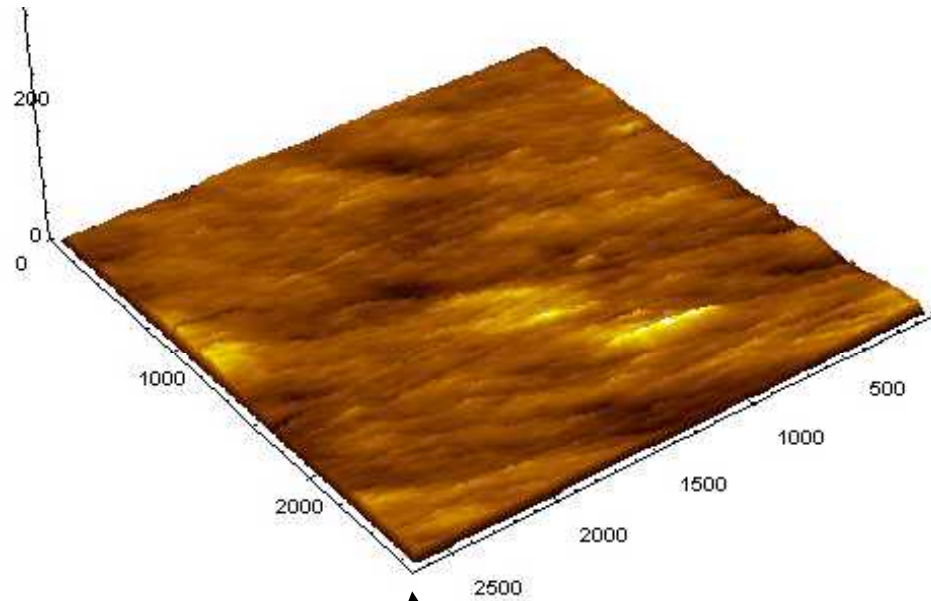
# Effect of Surface Roughness on Adhesion



# Effect of Surface Roughness on Adhesion



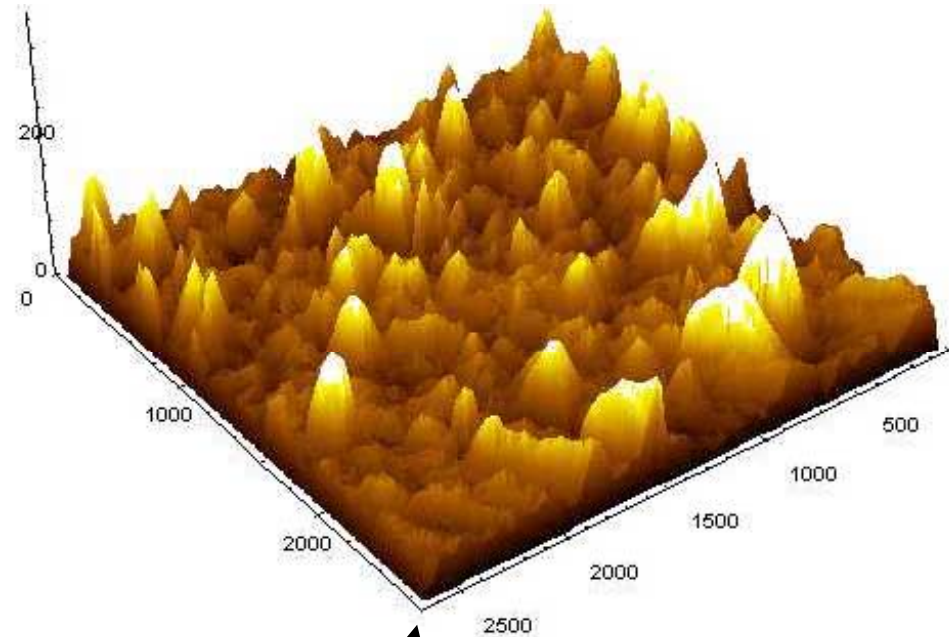
# Effect of Surface Roughness on Adhesion



**Low pH**

silicon (with native oxide)

- \* not etched
- \* atomically smooth
- \* strong adhesion w/ PSL



**High pH**

silicon (with native and grown oxide)

- \* anisotropically etched (KOH)
- \* rough surface (35 nm peaks)
- \* weak adhesion w/ PSL

# Conclusion--1<sup>st</sup> Generation Model

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• **Ideal vdW models and Equilibrium Models (JKR, DMT, MP) are limited to:**

- geometric (spherical particles interacting with flat surfaces)
- morphology (smooth systems)

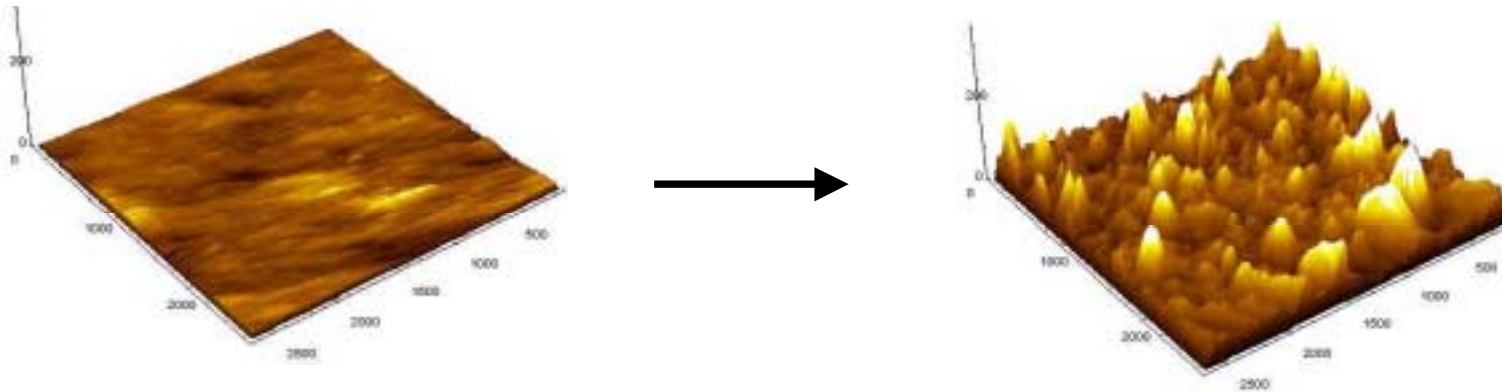
• **1<sup>st</sup> Generation model incorporates these factors**

# Conclusion--1<sup>st</sup> Generation Model (cont'd)

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• **Aqueous media can help prevent or promote surface adhesion by:**

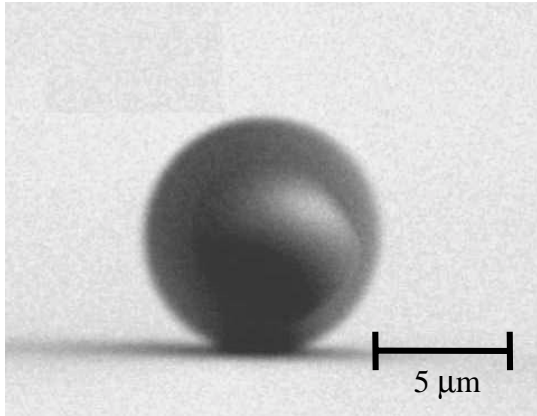
- Changing the surface chemistry of the interacting surfaces
- Changing the morphology of the interacting surfaces



• **Particle and surface roughness is a controlling factor in particle adhesion**

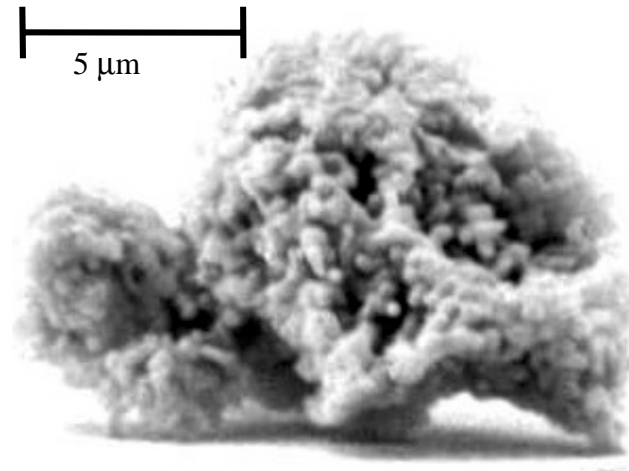
# Second Generation Model

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## 1<sup>st</sup> generation model

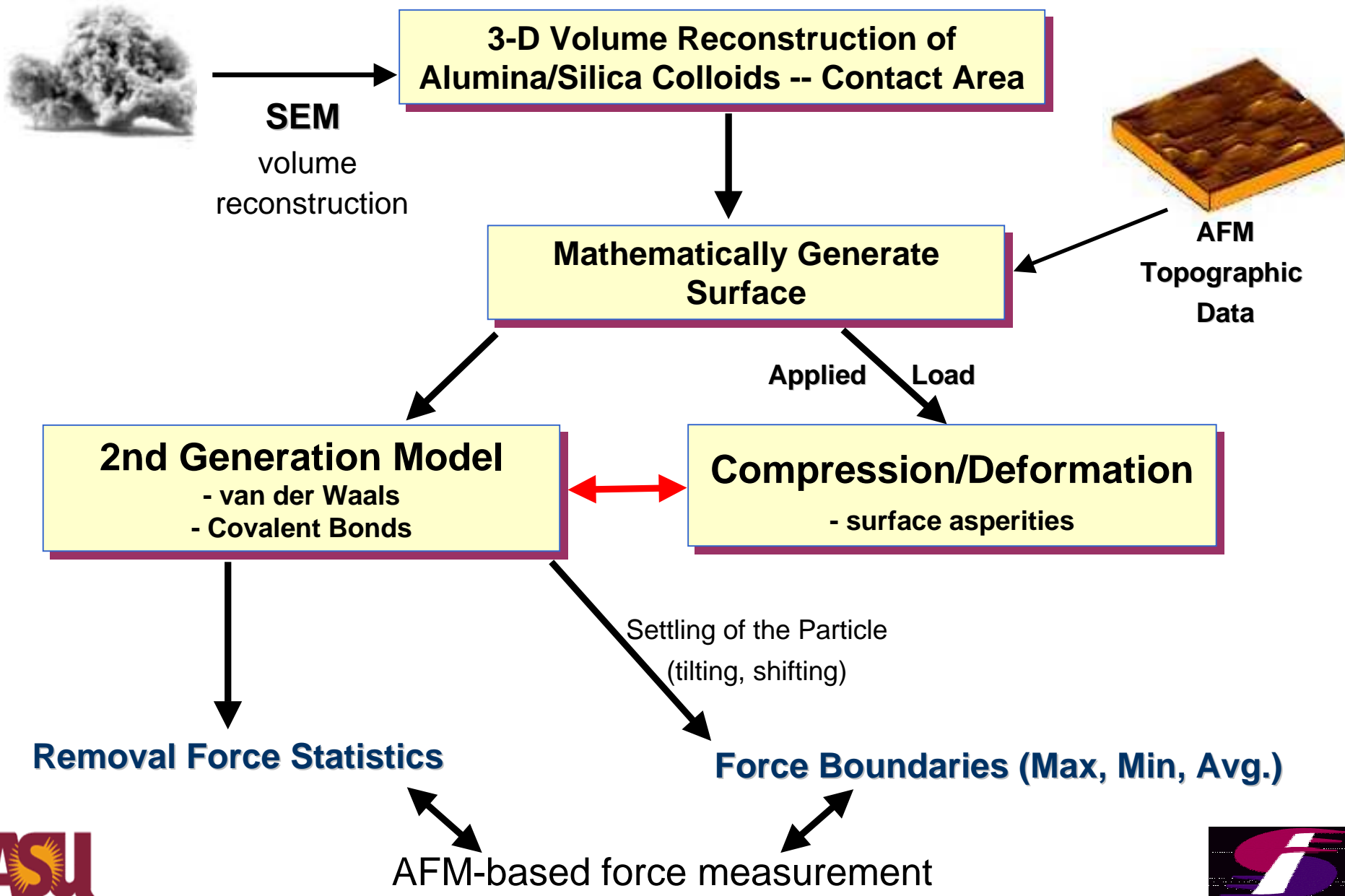
- ideal geometries
- ability to model contact area
- uniform microscopic morphology



## 2<sup>nd</sup> generation model

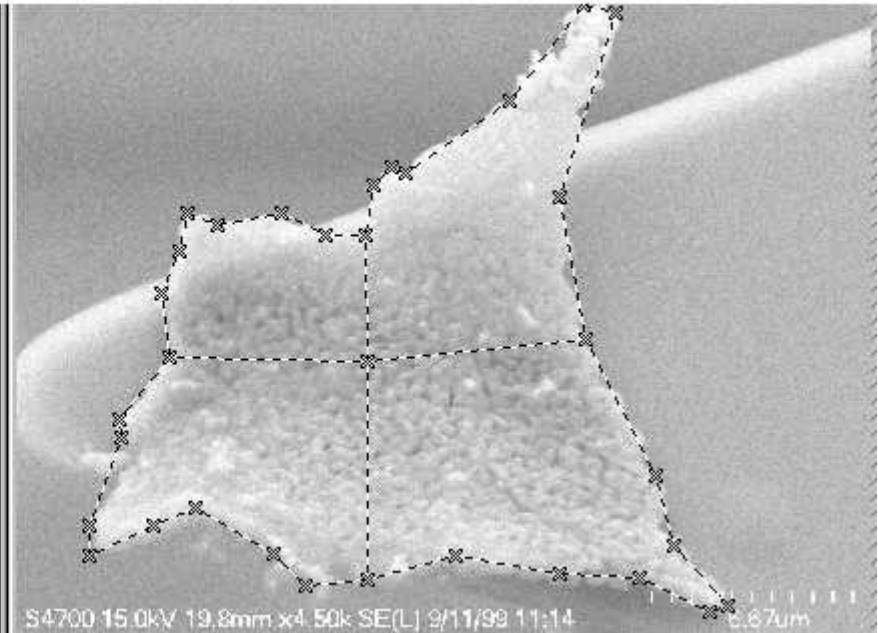
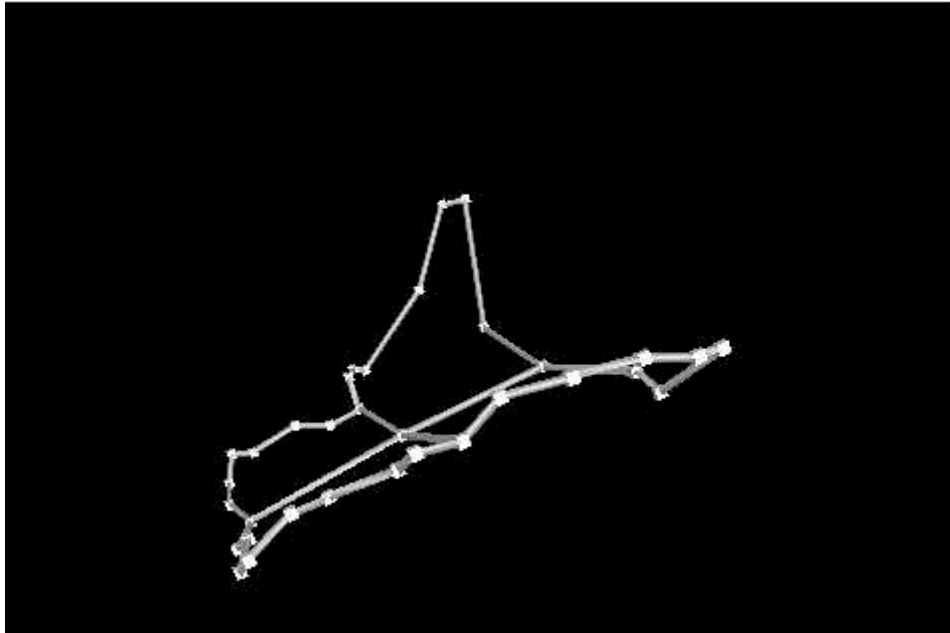
- any geometry
- random microscopic morphology
- compression/deformation of surface asperities
- chemical heterogeneities
- bonding
- settling (tilting, shifting)
- **statistical information**

# Second Generation Model



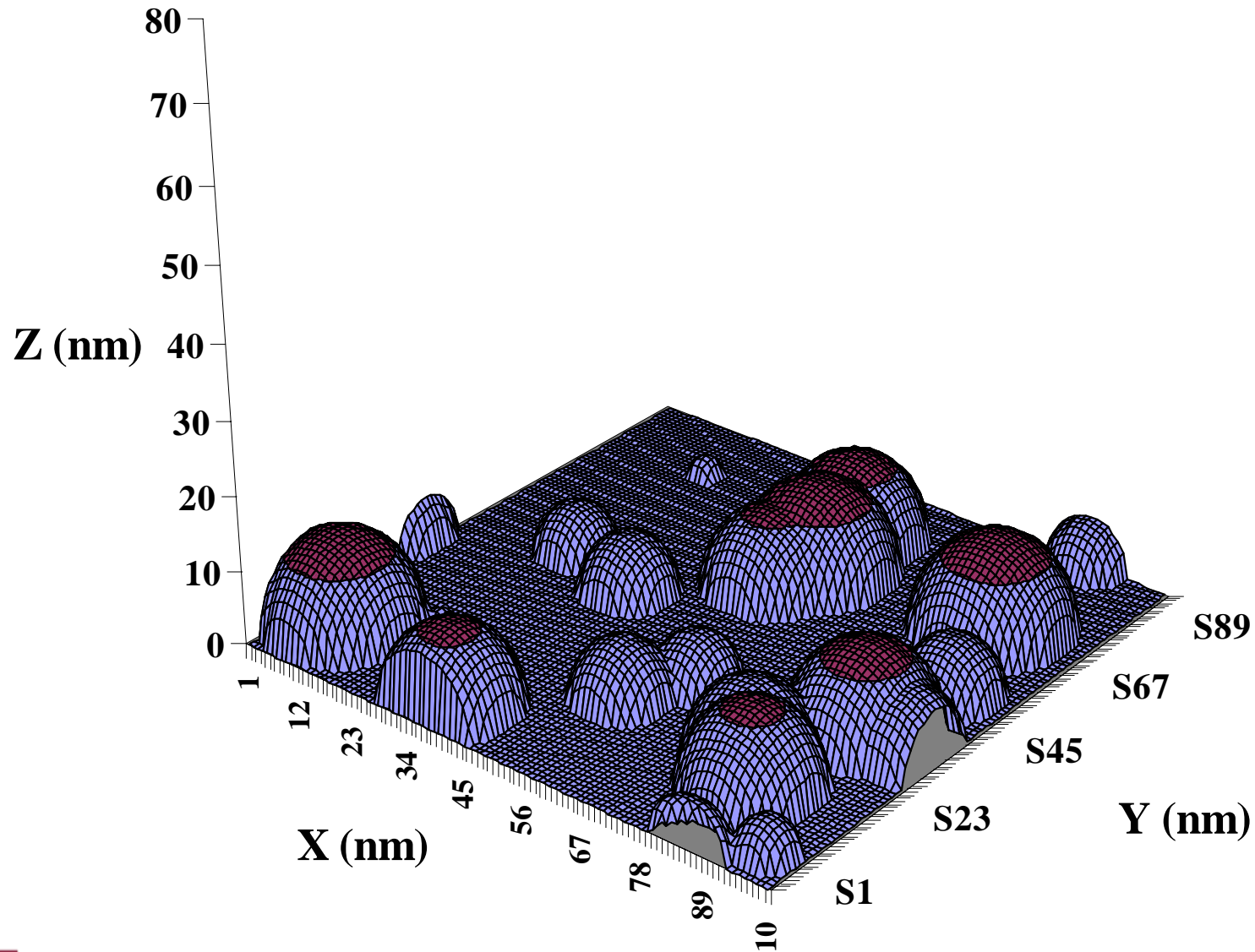
# 3-D Reconstruction

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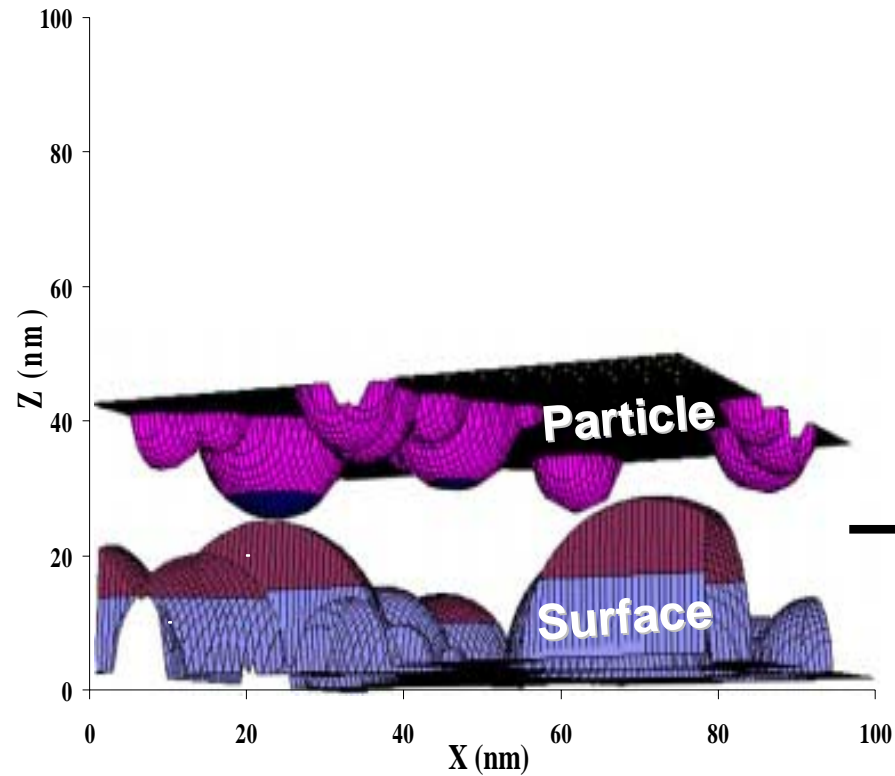




# Random Surface Generation



# Surface Interaction



**Cylindrical Volume Elements**

$$F_{attr} = - \frac{A \cdot (\text{Area cylinder})}{6 \cdot \pi \cdot D^3}$$

- Elements are placed every nm